		Derfinent Pages, Heart
	O	THER ART (Including Author, Title, Date, Pertinent Pages, Hest,
DE	AR	Bothra, S., et al., "Integration of 0.25 μ m Three and Five Reversible Bothra, S., et al., "Integration of 0.25 μ m Three and Five Reversible Bothra, S., et al., "Integration of 0.25 μ m Three and Five Reversible Bothra, S., et al., "Integration of 0.25 μ m Three and Five Reversible Bothra, S., et al., "Integration of 0.25 μ m Three and Five Reversible Bothra, S., et al., "Integration of 0.25 μ m Three and Five Reversible Bothra, S., et al., "Integration of 0.25 μ m Three and Five Reversible Bothra, and Five Reversible Bothra, S., et al., "Integration of 0.25 μ m Three and Five Reversible Bothra, and F
IAK	AS	Dobson, C.D., et al., "Advanced SiO ₂ Planarization Using Silding and 7 The Dobson, C.D., et al., "Advanced SiO ₂ Planarization Using Silding and 7 The Dobson, C.D., et al., "Advanced SiO ₂ Planarization Using Silding and 7 The Dobson, C.D., et al., "Advanced SiO ₂ Planarization Using Silding and 7 The Dobson, C.D., et al., "Advanced SiO ₂ Planarization Using Silding and 7 The Dobson, C.D., et al., "Advanced SiO ₂ Planarization Using Silding and 7 The Dobson, C.D., et al., "Advanced SiO ₂ Planarization Using Silding and 7 The Dobson, C.D., et al., "Advanced SiO ₂ Planarization Using Silding and 7 The Dobson, C.D., et al., "Advanced SiO ₂ Planarization Using Silding and 7 The Dobson, C.D., et al., "Advanced SiO ₂ Planarization Using Silding and 7 The Dobson, C.D., et al., "Advanced SiO ₂ Planarization Using Silding and 7 The Dobson, C.D., "Advanced SiO ₂ Planarization Using Silding and 7 The Dobson, C.D., "Advanced SiO ₂ Planarization Using Silding and Planarization Using Silding Silding and Planarization Using Silding
V . C	<u>ا</u>	Gengtant Oxide Films Deposited Usin
641	AT	McClatchie, S., et al., "Low Dielectric Constant Oxide Films Deposited Usin CVD Techniques", 1998 Proceedings Fourth International DUMIC'Conference, February 16-17, 1998, pp. 311-318.
1410	1	February 16-17, 1990, FF

Examiner

*Examiner

AΑ

AΒ

AC

AD

ΑE

AF AG AHΑI ΑJ ΑK

> ALMA AN ΑO ΑP

Initial

Date Considered

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with your communication to applicant.

					Sì	neet <u>2</u>	_ of _2_ s	sheets
FORM PTO-1					ket No		Serial No.	
U.S. Depar	rtment	oi Commerce	e, Patent a	nd Trademark Office	00-654			
INFO	RMATI	ON DISCLOSUR	RE STATEMENT	I BY APPLICANT	Applicant	ts		
	(Us	e several sh	eets if ned	cessary)	Wilbur G	. Catabay	et al.	
					Filing Da Herewith	ate	Group	
			11	C. Dahamb Dammada	nerewith		Unknown	
*Examiner	Τ	Document	1	.S. Patent Documents		Γ		
Initial		Number	Date	Name	Class	Subclas	Filing D If Appropri	
	BA							
	BB							
	BC							
	BD							
	BE							
	BF							
	BG	1						
	ВН		<u> </u>			1		
	BI				<u> </u>			
	BJ							
	BK	<u> </u>	<u> </u>		<u> </u>			
			Fore	eign Patent Documents	 			
·		Document	Date	Country	Class	Subclas	Translatio	
		Number	-	Country	Class	Subclas	s Yes	No
	BL							ļ
	BM			-				
	BN	70				-		<u> </u>
	во							
	BP							
	- 1			thor, Title, Date, Pe				
LARE	BR	<u>Semicondu</u>	ra, "Low-k ctor Interr 122, and 1	Dielectrics: Will S national, Vol. 23, No 124.	pin-On or . 6, June,	CVD Prev , 2000, p	ail?", p. 108-110,	114,
LARE LARE	BS	Peters, Lau <u>Internati</u> and 74.	ra, "Pursui <u>onal</u> , Vol.	ing the Perfect Low-k 21, No. 10, Septembe	Dielectri r, 1998, p	lc", <u>Semi</u> pp. 64-66	<u>conductor</u> , 68, 70, 72	2,
	BT							
Examiner /	1.1	-	Date Consi	dered 71.				

*EXAMINER: Initial is reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with your communication to applicant.

Date Considered

sheets Sheet Serial No. Docket No. FORM PTO-1449 (Modified) U.S. Department of Commerce, Patent and Trademark Office 00-654 Applicants INFORMATION DISCLOSURE STATEMENT BY APPLICANT Wilbur G. Catabay et al (Use several sheets if necessary) Group Filing Date Unknown U Herewith U.S. Patent Documents Filing Date Subclass Document Class *Examiner Name Appropriate Date Number Initial 7/24/97 1.2 134 Chien et al. 5/18/99 5,904,154 AΑ 4/26/96 192.35 204 Bersin et al. 3/16/99 5,882,489 AB6/6/97 725 438 Chao et al. 1/12/99 5,858,879 AC 1/15/60 223.5 23 Ling 12/12/61 3,012,861 AD 4/9/62 46.5 260 Kriner 4/13/65 3,178,392 \mathbf{AE} 8/8/72 287 106 Ritchie 8/27/74 3,832,202 AF 4/6/72 220 427 Läufer et al. 11/18/75 3,920,865 AG 11/28/86 405 428 Glajch et al. 11/10/87 4,705,725 AΗ 12/18/90 405 428 Ohnaka et al. 3/16/93 5,194,333 ΑI 8/5/97 59 257 Kuo 2/23/99 5,874,745 ΑJ ΑK Foreign Patent Documents Translation No Subclass Yes Class Country Date Document Number ALMA AN ΑO AP OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.) AR. AS Date Considered Examiner /

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with your communication to applicant.

Serial No. Docket No. FORM PTO-1449 (Modified) U.S. Department of Commerce, Patent and Trademark Office 00-654 Applicants INFORMATION DISCLOSURE STATEMENT BY APPLICANT Wilbur G. Catabay et al. (Use several sheets if necessary) Group Filing Date Unknown Herewith U.S. Patent Documents Filing Date Subclass Document Class Name *Examiner Appropriate Date Number Initial 11/6/98 781 438 You et al. 5,23/00 6,066,574 ΒA 10/22/96 404 438 4/18/00 Nam 6,051,477 BB 9/11/97 624 438 Tsai et al. 2/15/00 6,025,263 ВC 9/5/96 411 257 Hao et al. 8/17/99 5,939,763 BD8/13/96 634 257 Kapoor et al. 1/26/99 5,864,172 BE 12/23/94 235 437 Yoon et al. 11/18/97 5,688,724 BF 6/28/93 238 437 Kapoor et al. 11/28/95 5,470,801 BG 6/24/93 28 437 Joyner 11/15/94 5,364,800 BH4K 11/24/86 49 357 Malaviya et al. 9/13/88 4,771,328 ΒI 3/13/69 201 117 Yamazaki 3/28/72 3,652,331 ВJ ВK Foreign Patent Documents Translation No Subclass Yes Class Country Date Document Number BLBM RN во BP OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.) Koda, Seiichiro, et al., "A Study of Inhibition Effects for Silane Combustion by Additive Gases", Combustion and Flame, Vol. 73, No. 2, BR August, 1988, pp. 187-194. BS BT Date Considered Examiner *EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy

of this form with your communication to applicant.

FORM PTO-1449 (Modified) U.S. Department of Commerce, Patent and Trademark Office					Docket No. Serial No			rial No.	
U.S. Depar	Cilienc	OI COMMETCE	, Patent an	Id Trademark Office	00-654				
INFO	RMATIC	ON DISCLOSUR	E STATEMENT	BY APPLICANT	Applicant	:s			
	(Use	e several she	eets if nec	essary)	Wilbur G.	Catabay	, et	: al.	
					Filing Da	ıte		oup	
					Herewith		Un	ıknown	
	Ť	1	<u>U.</u>	S. Patent Documents		γ			
*Examiner Initial		Document Number	Date	Name	Class	Subclas	3S	Filing Da If Appropria	
IAK	CA	5,628,871	5/13/97	Shinagawa	438	514		6/24/94	
IAK	СВ	6,153,524	11/28/00	Henley et al.	438	691	\perp	7/28/98	
LAK	CC	6,051,073	4/18/00	Chu et al.	118	723		6/3/98	
IAC	CD	5,580,429	12/3/96	Chan et al.	204	192.38		6/7/95	
LAIC	CE	5,558,718	9/24/96	Leung	118	723E		4/8/94	
LAR	CF	6,037,248	3/14/00	Ahn	438	619		6/13/97	
LAR	CG	5,675,187	10/7/97	Numata et al.	257	758		5/16/96	
LATE	CH	5,559,367	9/24/96	Cohen et al.	257	77		7/12/94	
IAR	CI	5,376,595	12/27/94	Zupancic et al.	501	12		8/28/92	
	CJ								
	CK	,							
			Fore	eign Patent Documents	ı				
	Г						T	ranslation	1
		Document Number	Date	Country	Class	Subclas	s	Yes	No
AL	CL	2000-267128	9/29/00	Japan	G02F	1/136	_	X-Abstract Only	
	CM					<u></u>	\dashv		
	CN		-		-		_	-	
	CO				-		\dashv		
	CP					<u> </u>	Щ		
	07	THER ART (Inc	cluding Aut	hor, Title, Date, Pe	rtinent Pa	iges, Etc	2.)		
	CR								
	cs)			. 1000	2.0			
	CT								
Examiner	2:1.	10	Date Consi	dered High					
*EXAMINER: MPEP 609; D of this for	raw l	ia if refer ine through th your commu	citation if	dered, whether or not f not in conformance c applicant.	citation and not c	is in co	onf d.	ormance wi Include o	
				EE					

Sheet Serial No. Docket No. FORM PTO-1449 (Modified) U.S. Department of Commerce, Patent and Trademark Office 09/884,736 00-654 O P EINFORMATION DISCLOSURE STATEMENT BY APPLICANT Applicant Wilbur G. Catabay et al. (Use several sheets if necessary) Filing Date Group AUG 2 7 2001 Unknown June 19, 2001 U.S. Patent Documents Filing Date Document *Examiner Class Subclass Name Date Appropriate Number Initial 2/2/90 238 437 Lee et al. 5,314,845 5/24/94 AA 6/10/97 438 669 Sengupta et al. 6/22/99 5,915,203 ABАC ΑD ΑE AF AG ΑH ΑI ΑJ AΚ Foreign Patent Documents Translation No Yes Class Subclass Country Document Date Number Х 21/312 H 01 L Germany 7/1/99 DE 198 04 375 A1 N/A23/532 H 01 L 4/10/96 Europe EP 0 706 ΑM 216 A2 N/A 21/312 H 01 L Europe 10/13/99 EP 0 949 ΑN 663 A2 X-Abstract 21/90 H 01 L 1/8/88 Japan Only 63003437 ΑO N/AC 23 C PCT 8/19/99 WO ΑP 99/41423 OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.) AR AS AT7/18/02 Date Considered Examiner

Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with your communication to applicant.

		De	eket No.	eet <u>1</u>		rial No.	
and Tr	and Trademark Office)-654 -			/884,736	
אַר מי יווין,	APPLICANT		plicant				
ecess	OIP E		llbur G.	Catabay	, et	al.	
LUGBBA	AND S I SOUN		Filing Date		1	oup	
	MIR 5		une 19, 2	2001	Un	known	
U.S. F	eachity Note ments						
	Name.		Class	Subcla	ss	Filing Da If Appropria	
00 Le	ee et al.	丁	438	789		10/10/97	
		\Box					
		_		<u> </u>		 	
		_		 			
				 		 	
				 		-	
				 		 	
			 	 			
			 				
+							
oreig	n Patent Documen	ıts					
						Translati T	
	Country		Class	Subcl	ass	Yes	No
			 	T			
			<u> </u>				
+							
+	,						
İ							

Country Date Document Number MA ΑN ΑO

OTHER ART (Including Author, Title

Sugahara, Satoshi, et al., "Cher AR Silica Films for Interlayer Die International Meeting, Electrochemical Societ 1999, Abstract No. 746.

FORM PTO-1449 (Modified)

AA ΑB AC ΑD ΑE AF AGHAΑI ΑJ AΚ

*Examiner

Initial

U.S. Department of Commerce, Patent and Trademark

Document

6,043,167

Number

INFORMATION DISCLOSURE STATEMENT BY APPL

(Use several sheets if necess

Date

3/28/2000

Examiner

Date Considered

7/18

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with your communication to applicant.



Sheet



1

Approved for u Ligh 10/31/99. OMB 0651-0031

Patent and Trademark Office: PARTMENT OF COMMERCE

Under the Paperwork Reduction Act of 1995, no persons are required to respond to a collection of information unless it displays a valid OMB control number.

PTO/SB/08A (10-96)

INFORMATION DISCLOSURE STATEMENT BY APPLICANT

of

Complete if Known 09/884,736 Application Number June-19, 2001 Filing Date Wilbur Catabay First Named Inventor Group Art Unit Examiner Name / 00-654 Attorney Docket No.

U.S. PATENT DOCUMENTS								
Examiner Initials	Cite No.	U.S. Patent Number	Document Kind Code (if known)	Name of Patentee or Applicant of Cited Document	Date of Publication of Cited Document MM-DD-YYYY	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear		
LAC		5,989,998		Sugahara et al.	11-23-1999	·		
AK AK		6,054,379		Yau; Wai-Fan (Mountain Vie	04-25-2000			
		6,215,087		Akahori et al.	04-10-2001			
(AC)		5,930,655		Cooney, III; Edward C. (Jeric	07-27-1999			
M		6,043,145		Suzuki et al.	03-28-2000			
M		6,063,702		Chung	05-16-2000			

Date Examiner considered signature

Burden Hour Statement: This form is estimated to taken 2 hours to complete. Time will vary depending upon the needs of the individual case. Any comments on the time you are required to complete this form should be sent to the Chief Information Officer, Patent and Trademark Office, Washington, DC 20231. DO NOT SEND FEES OR COMPLETED FORMS TO THIS ADDRESS. SEND TO: Assistant Commissioner for Patents, Washington, DC 20231.

